

L-Edit CAD Software

L-Edit Layout Editor software by Mentor Graphics

Computer Aided Design Training with L-Edit software is conducted via Zoom. Please e-mail ledit-training@cnf.cornell.edu to request training. Training is usually taught by Alan Bleier or Karlis Musa.

Description:

L-Edit is a layout editor for photolithography, electron beam lithography, or dot-matrix printing. It runs on Windows computers in the CNF CAD room, the cleanroom, and 2nd floor labs.

L-Edit is used to design devices and produce intermediate files in an industry-standard format.

For the dot-matrix printer the intermediate format is CIF, and the copy of L-Edit in the dot-matrix printer lab must be used to export the file to CIF format.

For electron beam lithography and photolithography the intermediate file format is GDSII.

Contact managers of each e beam or mask making tool to learn how to convert from GDSII to the native file format for that tool. The e beam tools are the JEOL 6300FS and the JEOL 9500FSZ. The mask makers are the Heidelberg DWL2000 laser pattern generator and the Heidelberg DWL66 laser pattern generator.

Capabilities:

- Large, useful manual available from Help menu
- Boolean and derived layer operations; subtract, grow and shrink on groups of objects
- Design navigator for easy traversal of design hierarchy
- Area calculator (in Tools -> Add-Ins)
- Cross-section viewer to simulate a set of simplified process steps and visualize vertical structure of a device
- Support for parameterized cells called T-Cells
- User-programmable interface (UPI) with C/C++ syntax

Documentation:

- [Tanner EDA L-Edit Layout Editor web site](#)
- [Handout and quick reference for CAD at CNF using L-Edit](#)
- [Using L-Edit v2020](#)